

SPECIFICATION AMENDMENTS

Please replace the text on page 1, lines 10-19 with the following:

The present application claims benefit of U.S. Patent Application No. 60/411,357, filed 16 September 2002, entitled, "METHODS AND APPARATUS FOR THERMAL FLUX MEASUREMENTS." The present application is related to U.S. Patent Application No. 09/643,614, filed on 22 August 2000, now United States Patent 6,691,068, U.S. Patent Application No. 09/816,648, filed on 22 March 2001, now United States Patent 6,542,835, U.S. Provisional Patent Application No. 60/285,439 titled "METHODS, APPARATUS, AND COMPUTER PROGRAM PRODUCTS FOR OBTAINING DATA FOR PROCESS OPERATION, OPTIMIZATION, MONITORING, AND CONTROL," filed 19 April 2001, case Docket No. AWS-003. All of these applications are incorporated herein, in their entirety, by this reference.

Please replace the text of page 5 line 2 with the following:

chemical vapor deposition, and sputter deposition ~~sputter deposition~~, and. In the following description of